

Substitute Form PTO-1449 (Modified)  <b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney Docket No. <b>20228-0013US1</b>	Application No. <b>10/580,698</b>
	Applicant <b>Damian Fiolka et al.</b>		
	Filing Date <b>November 29, 2006</b>	Group Art Unit <b>2872</b>	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	1	6483573	11/19/2002	Schuster			
	2	2009/0115989	5/7/2009	Tanaka			
	3	2009/0128796	5/21/2009	Tanaka			
	4	2010/0141921	6/10/2010	Omura			
	5	2010/0141926	6/10/2010	Omura			
	6	2010/0142051	6/10/2010	Omura			

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	7	KR 2000-0076783	12/26/2000	KR			See 1	
	8	JP 7-142338	6/2/1995	JPO			Abstract only	
	9	JP 2001-135560	5/18/2001	JPO			X	
	10	JP 2005-108925	4/21/2005	JPO			Abstract only	

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	11	Himel et al., "Design and fabrication of customized illumination patterns for low ki lithography: a diffractive approach," Optical Microlithography XIV, Christopher J. Proglor, Editor, Proceedings of SPIE Vol. 4346 (2001).

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	